JAN 1 0 2005 W

PATENT 3811-0122P

## IN THE U.S. PATENT AND TRADEMARK OFFICE

Applicant:

Yi Yeol LYU et al.

Conf.:

4059

Appl. No.:

10/621,380

Group:

1712

Filed:

July 18, 2003

Examiner: M. G. MOORE

For:

SILOXANE-BASED RESIN AND METHOD FOR

FORMING INSULATING FILM BETWEEN

INTERCONNECT LAYERS IN SEMICONDUCTOR

DEVICES BY USING THE SAME

## LARGE ENTITY TRANSMITTAL FORM

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

January 10, 2005

Sir:

Transmitted herewith is an amendment in the above-identified application.

The enclose	ed document	is	being	trans	smitted	via	the	Certificate
of Mailing	provisions	of	37 C	.F.R.	§ 1.8.			

The enclosed document is being transmitted via facsimile.

The fee has been calculated as shown below:

	CLAIMS REMAINING AFTER AMENDMENT	HIGHEST NUMBER PREVIOUSLY PAID FOR			PRESENT EXTRA	RATE	ADDITIONAL FEE
TOTAL	12	- 20		=	, 0	\$50	\$0.00
INDEPENDENT	2	_	3		0	\$200	\$0.00
FIRST PRESE	NTATION OF A	MULT	TIPLE DEPENDE	IT CL	AIM	\$360	\$0.00
	<del></del>					TOTAL	\$0.00

Petition for one (1) month(s) extension of time pursuant to 37 C.F.R. §§ 1.17 and 1.136(a). \$120.00 for the extension of time.
No fee is required.
Check(s) in the amount of \$120.00 is(are) enclosed.
Please charge Deposit Account No. 02-2448 in the amount of \$0.00. This form is submitted in triplicate.

If necessary, the Commissioner is hereby authorized in this, concurrent, and future replies, to charge payment or credit any overpayment to Deposit Account No. 02-2448 for any additional fees required under 37 C.F.R. § 1.16 or under 37 C.F.R. § 1.17; particularly, extension of time fees.

Respectfully submitted,

BIRCH, STEWART, KOLASCH & BIRCH, LLP

RA\_\_

Joseph A. Kolasch, #22,463

JAK/REG:jis

3811-0122P

Attachment(s)

P.O. Box 747

Falls Church, VA 22040-0747

(703) 205-8000



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## AMENDMENT UNDER 37 C.F.R. § 1.111

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

January 10, 2005

Sir:

In reply to the Office Action dated September 10, 2004, the period for response having been extended by one (1) month until, January 10, 2005, the following amendments and remarks are respectfully submitted in connection with 120,00 OP the above-identified application.

This reply includes a claim set as amended and remarks.

01/11/2005 FFANAEIA Q0000Q61 10624380

120.60 OF 01 FC:1251

01/11/2005 FFANAEIA 00000113 10621380